

Form PTO-1449 (REV. 1/06)		US Dept. of Commerce PATENT & TRADEMARK OFFICE		ATTY DOCKET NO. 126821		APPLICATION NO. 10/565,968	
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)				APPLICANT(S) Satoshi TAKEI et al.			
				FILING DATE January 31, 2006		GROUP	
FOREIGN PATENT DOCUMENTS							
Examiner Initials	Cite No.	Document Number	Date	Country	With English Abstract	With English Translation	
RA	1.	JP-A-2000-294504	10-2000	Japan	X	X	
RA	2.	JP-A-2002-47430	02-2002	Japan	X	X	
RA	3.	JP-A-2002-190519	07-2002	Japan	X	X	
RA	4.	WO 02/05035	01-2002	WIPO	X		
*	5.	JP-A-2002-128847	05-2002	Japan	X	X	
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RA	7.	JP-A-2000-264921	09-2000	Japan	X	X	
*	8.	JP-A-07-316268	12-1995	Japan	X	X	
RA	9.	JP-A-2002-105137	04-2002	Japan	X	X	
RA	10.	JP-A-10-221855	08-1998	Japan	X	X	
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RA	14.	Lynch, Tom et al., "Properties and Performance of Near UV Reflectivity Control Layers", US, in Advances in Resist Technology and Proceedings XI, Omkaram Nalamasu et., Proceedings of SPIE, 1994, Vol. 2195, pp. 225-229					
RA	15.	Taylor, G. et al., "Methacrylate Resists and Antireflective Coatings for 193 nm Lithography", US, in Microlithography 1999: in Advances in Resist Technology and Processing XVI, Will Conley ed., Proceedings of SPIE, 1999, Vol. 3678, pp. 174-185					
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EXAMINER R. Ash for				DATE CONSIDERED 2-2-07			
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

* Not enclosed

Date: May 15, 2006

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U.S. PATENT DOCUMENTS							
Examiner Initials	Cite No.	Document Number	Date	Name			
RA	17.	5,919,599	07-1999	Meador et al.			
RA	18.	5,693,691	12-1997	Flaim et al.			
RA	19.	6,686,124 B1	02-2004	Angelopoulos et al.			
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RA	22.	2002/0090452 A1	07-2002	Hong et al.			
RA	23.	2002/0123586 A1	09-2002	Hong et al.			
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